

DOCKET NO. SC0112WD

Please amend the subject application as follows:

IN THE SPECIFICATION:

On page 1, lines 1-2, amend the title as follows:

~~ELECTRONIC DEVICE FOR MANUFACTURING SYSTEM METHOD FOR
PROCESSING A LITHOGRAPHY MASK CONTAINER, SEMICONDUCTOR
MANUFACTURING SYSTEM, AND METHOD~~

Amend the paragraph on page 5 and extending to line 5 of page 6 as follows:

The term "using a mask in a process" (and its language variations) is intended to comprise at least one of the following actions:

- inserting mask 201 into container 200;
- removing mask 201 from container 200;
- in combination, inserting and removing multiple masks 201/202 (cf. FIG. 3);
- writing data to mask 201 (e.g., by adding a barcode label);
- reading data from mask 201 (e.g., reading the barcode label);
- exposing a semiconductor wafer (not illustrated) or any other work-product by sending electromagnetic radiation through mask 201;
- storing mask 201;
- transporting mask 201 from one location to another location within the wafer factory (cf. FIG. 3);
- manufacturing mask 201 ~~210~~;
- maintaining mask 201 ~~210~~ (e.g., cleaning);
- modifying mask 201 by changing its exposure properties (e.g., through aging);

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- damaging mask 201, disposing of mask 201, recycling mask 201, or any other action that removes mask 201 from the factory;
- testing and measuring the properties of mask 201, either directly (e.g., evaluating an exposure picture), or indirectly, (e.g., evaluating a wafer exposed to radiation by the mask);
- assigning an identifier for mask 201;
- assigning an identifier for a plurality of masks 201 (e.g., type classification); and
- transferring information that relates to mask 201 from a first electronic device in a first container to a further electronic device in a further container.

This action catalogue will be referred to later in connection with a method.

Amend the first full paragraph on page 6 at lines 6-25 as follows:

For example, and without the intention to be limiting, station 110/120 can be the following: a mask sorter for inserting the mask into the container, removing the mask from the container, inserting and removing multiple masks to and from the container; a lithography exposure tool for exposing a semiconductor wafer (not illustrated) or any other work-product by sending electromagnetic radiation through the mask (the main purpose of the mask); a transport tool (e.g., automated vehicle, robot), for transporting the mask from one location in the ~~factor~~ factory to another location in the ~~factor~~ factory, or for storing the mask, for writing data to the mask or reading data from the mask; a manufacturing tool for manufacturing the mask (preferably, outside the factory), for assigning a single identifier for a single mask or a single identifier to a plurality of masks; a metrology tool for testing and measuring the properties of the mask; a cleaning tool for removing

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contamination from the mask; or any other equipment inside or outside the factory that serves one or more actions referred to in the catalogue.

On page 22, lines 1-2, amend the title as follows:

~~ELECTRONIC DEVICE FOR~~ MANUFACTURING SYSTEM METHOD FOR
PROCESSING A LITHOGRAPHY MASK CONTAINER, ~~SEMICONDUCTOR~~
~~MANUFACTURING SYSTEM, AND METHOD~~